1st Announcement and Call for Papers

5-7 April 2017
Pacifico Yokohama
Yokohama, Japan

Photomask Japan 2017

The 24th Symposium on Photomask and NGL Mask Technology

Symposium Chair:
Prof. Masato Shibuya
Tokyo Polytechnic University

Abstract Due Date:
November 30, 2016

Camera-Ready Abstract Due Date:
February 1, 2017

Manuscript Due Date:
March 14, 2017

Concrete information will be announced at the 2nd Call for Papers.

Camera-ready abstracts and manuscripts are required of all accepted applicants and must be submitted in English.

Photomask Japan 2017 is the 24th international symposium on photomasks and NGL masks in Japan. The aim of the symposium is to bring together engineers and investigators from Japan and all over the world in the field of photomasks, NGL masks, and related technologies to discuss recent progress, applications, and future trends. The conference program will feature invited papers, contributed papers, poster sessions, and a rump session with panel discussion. Display opportunities will be provided to mask manufacturing materials, and equipment companies.

Papers are solicited on the following and related topics:

- **Materials of and for Photomasks**
- **Fabrication Process Steps and Equipment for Photomasks (Process and Equipment for Developing, Etching, Cleaning etc.)**
- **Photomask Writing Tools and Technologies**
- **Metrology Tools and Technologies**
- **Inspection Tools and Technologies**
- **Repairing Tools and Technologies**
- **Technologies and infrastructures for EUVL masks**
- **Mask Data Preparations, EDA and DFM**
- **Photomasks with RET: PSM, OPC, SMO and Multiple Patterning**
- **Photomask-relating Lithography Technologies**
- **NIL and masks for Patterned Media**
- **Photomasks for FPD**
- **DSA (Directed Self-Assembly)**
- **Strategies and Business Challenges: Cost, Cycle-Time, ML2 etc.**
- **Mask/Lithography related Technology in Academia (Poster Session)**

Abstract Submissions

All authors are *strongly encouraged* to submit their abstract by the due date, November 30 2016 via the PMJ official website.
Abstract submission Web page will be opened from October 2016 at:

http://www.photomask-japan.org/

Further information and instruction will be available from 2nd Announcement & Call for Papers, which will be published around September, 2016

***Please do not send the abstract by e-mail or FAX.**

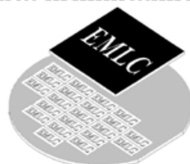
Conference Site

Conference site of Photomask Japan 2017 will be "Annex Hall" at Pacifico Yokohama

Sponsored by

SPIE.

Co-sponsored by



For more information, contact:
Photomask Japan Secretariat
c/o JTB Communication Design, Inc.
Celestine Shiba Mitsui Bldg.,
3-23-1 Shiba, Minato-ku, Tokyo, 105-0014
Tel: +81-3-5657-0777
Fax: +81-3-3452-8550
E-mail: pmj@jtbcom.co.jp
Web: http://www.photomask-japan.org/
Or
SPIE Technical Program Department
Phone: +1/360/676-3290
Fax: +1/360/647-1445
E-mail: spie@spie.org